

10. (New) The method according to claim 1, wherein said step of adjusting the content of particles includes cleaning an interior of a chamber of the film deposition system in which the film deposition process occurs using a dust cloth that produces no more than 1000 particles/cfm.

C1
11. (New) The method according to claim 1, wherein said step of adjusting the content of particles includes cleaning an interior of a chamber of the film deposition system in which the film deposition process occurs using a dust cloth that produces no more than 300 particles/cfm.

12. (New) The method according to claim 9, wherein said step of adjusting the content of particles further includes pumping out the chamber after cleaning to remove floating particles within the chamber.
